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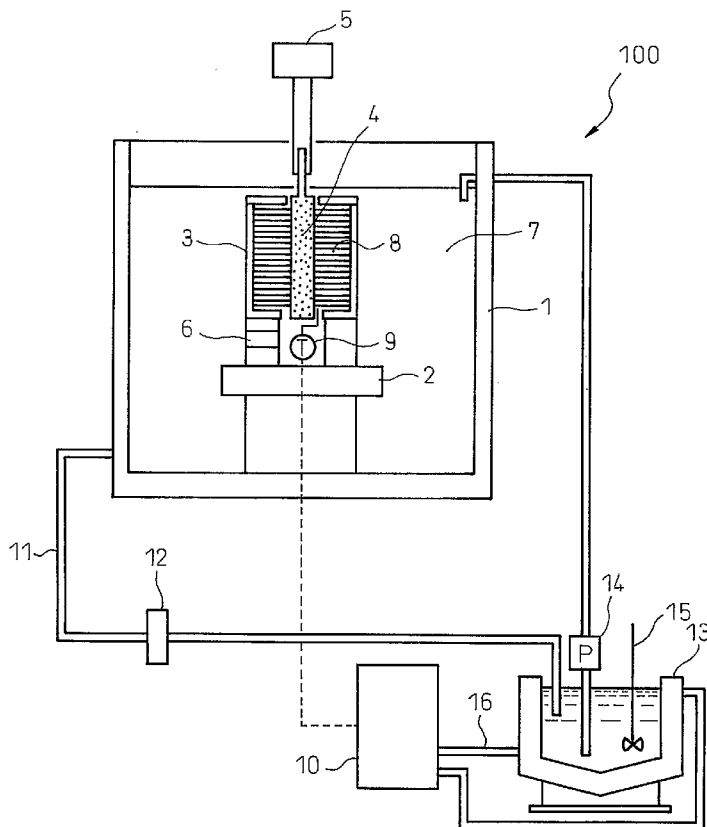
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(54) Title: METHOD OF POLISHING THE INNER PERIPHERAL END SURFACES OF SUBSTRATES FOR A RECORDING MEDIUM USING A BRUSH



(57) Abstract: The object of the invention is to provide a method of polishing the inner peripheral end surfaces of substrates while maintaining a sufficiently high working precision at the time of polishing the inner peripheral end surfaces of a plurality of disk-like substrates for a recording medium. According to the invention, there is provided a method of polishing the inner peripheral end surfaces of disk-like substrates for a recording medium using a brush comprising: providing a plurality of disk-like substrates for a recording medium having a circular hole at the central portion thereof thereby forming an inner peripheral end surface, and stacking them while aligning the circular holes to form an object to be polished having the circular hole at the central portion thereof; bringing a polishing material slurry containing a polishing material into contact with the object to be polished; and inserting a polishing brush having brush hairs studded on the periphery of a rod-like shaft into the circular hole of the object to be polished in a state where the slurry is brought into contact with the object to be polished, and rotating the polishing brush with the shaft as a center axis to polish the inner peripheral end surfaces of the substrates; wherein the polishing material slurry is controlled to remain at a constant temperature.



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